



Substitute for form 1449A/PTO				Complete if Known	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT				Application Number	10/687,288
				Filing Date	October 15, 2003
				First Named Inventor	Wang Yueh
				Art Unit	1756
				Examiner Name	Daborah Chacko Davis
Sheet	1	of	1	Attorney Docket Number	42P17301

NON PATENT LITERATURE DOCUMENTS			
Examiner Initials*	Cite No.†	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T*
DCD		LAMMERS, DAVID, "Euro, Japan go to extremes for EUV," EE Times, 10/18/2002, 6 pages	
DCD		ITO, H., "Chemical amplification resists: History and development within IBM," http://researchweb.watson.ibm.com/journal/rd/411/ito.txt , 1997 IBM, 12 pages	
DCD		"Introduction to Electron Beam Lithography," http://dot.cbe.gatech.edu/henderson/introduction_to_electron_beam_lithography.htm , 13	/dcd/ 09/01/2010
DCD		Definition of "PHOTORESIST" from Wikipedia, 2003, one page	
DCD		MEDEIROS, D.R., ET AL., "Recent progress in electron-beam resists for advanced mask-making," IBM J. RES. & DEV. vol 45, no. 5, 09/2001, pps. 639-650	
DCD		COBB, JONATHAN, ET AL., "Controlling line-edge roughness to within reasonable limits," Proceedings of SPIE Vol. 5039 (2003), pps. 376-383	
DCD		LINTON, T., ET AL., "Determination of the Line Edge Roughness Specification for 34 nm Devices," TCAD Division, Intel Corporation, 2002 IEEE, pps. 303-306	
DCD		STEWART, MICHAEL D., ET AL., "Diffusion Induced Line Edge Roughness," Advances in Resist Technology and Processing XX, Proceedings of SPIE Vol. 5039, 2003, pps. 415-422	/dcd/ 09/01/2010

Examiner Signature	/Daborah Chacko-Davis/	Date Considered	09/21/2006
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*Examiner: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication.

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